

REMARKS

Upon entry of this Preliminary Amendment, independent claim 36 is amended, claim 42 is cancelled without prejudice or disclaimer, and claims 43 and 44 have been added. It is believed that the foregoing amendments and additions add no new matter to the present application.

Applicants have attached hereto a Declaration by Dr. Harry P Gillis an expert in the field of surface sciences and dry etching. Applicants have claimed apparatus for low-damage anisotropic dry etching of a substrate, wherein electrons having kinetic energy less than 100 electron-volts are attracted to the substrate and etch material therefrom. Dr. Gillis declares that the cited art of record disclose conventional ion etching plasma reactors, not an electron etching reactor as claimed by Applicants.

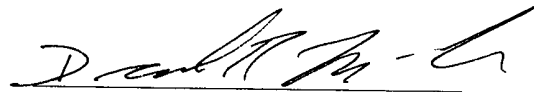
It is hereby respectfully requested that the Examiner enter the Amendment to the above-referenced patent application. Should there be any questions or comments concerning the amendments or remarks referenced herein, the Examiner is respectfully requested to contact the undersigned attorney.

Respectfully submitted,

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